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US Patent Nr.	Title	Assignee	Filed	Date of Patent
<a href="#">6429135</a>	Method of Reducing Stress Between a Nitride Spacer and a Substrate	UMC	1/5/01	8/6/02
<a href="#">6429538</a>	Method for Making a Novel Graded Silicon Nitride / Silicon Oxide (SNO) Hard Mask for Improved Deep Submicrometer Semiconductor Processing	TSMC	8/2/01	8/6/02
<a href="#">6433298</a>	Plasma Processing Apparatus	TEL	9/19/00	8/13/02
<a href="#">6451647</a>	Integrated Plasma Etch of Gate and Gate Dielectric and Low Power Plasma Post Gate Etch Removal of High-k Residual	AMD	3/18/02	9/17/02
<a href="#">6452400</a>	Method of measuring Negative Ion Density of Plasma and Plasma Processing Method and Apparatus for Carrying out the Same	TEL	6/19/200	9/17/02
<a href="#">6455433</a>	Method for Forming Square-Shouldered Sidewall Spacers and Devices Fabricated	TSMC	3/30/01	9/24/02
<a href="#">6463875</a>	Multiple Coil Antenna for Inductively-Coupled Plasma Generation Systems	LAM	11/15/00	10/15/02